

#1412 / [Signature]

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Smith, et al.

Docket No: TI-25250

Serial No: 09/199,829

Examiner: K. Eaton

Conf. No: 4119

Art Unit: 2823

Filed: 11/25/98

For: HYDROGEN PLASMA PHOTORESIST STRIP AND POLYMERIC RESIDUE  
CLEANUP PROCESS FOR OXYGEN-SENSITIVE MATERIALSRESPONSE PURSUANT TO 37 CFR 1.116Assistant Commissioner for Patents  
Washington, DC 20231

FACSIMILE CERTIFICATE UNDER 37 C.F.R. § 1.8(a)  
I hereby certify that the above correspondence is being  
transmitted by facsimile to: Assistant Commissioner for  
Patents, Attn: Kurt Eaton, Art Unit 2823, 703-308-7722 on  
11-16-01

  
Ann Trent

Dear Sir:

Responsive to the Office Action mailed September 25, 2001, in connection with  
the above identified application, Applicants respectfully submit the following remarks.

REMARKS

Claims 1, 4-6 and 25-31 were rejected under 35 U.S.C. 103(a) as being  
unpatentable over Akram in view of Irving. In rejecting the claims the examiner stated  
that Irving et al. teaches that any one of a number of gases such as hydrogen may be  
used. The examiner also cites Merck & Co v. Biocraft Laboratories, 874 F.2d 808 for  
the proposition that "[a] reference may be relied upon for all that it would have